

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	9	Oikari-j\$.in.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
2	BRS	L2	77	gast-t\$.in.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
3	BRS	L3	1281	chang-l\$.in.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
4	BRS	L4	1363	11 or 12 or 13	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
5	BRS	L5	90390	(reduce or reducing or reduce or reduction or inhibit or inhibiting or inhibited or inhibition or lower or lowering or lowered or lowering or minimize or minimizing or minimized or eliminate or eliminating or eliminated or elimination) adj10 (charge or charge adj3 buildup or charge adj3 build-up or electric adj3 (charge or discharge) or electrostatic adj3 (charge or discharge) or "ESD")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
6	BRS	L6	198350	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or rinse or rinsed or rinsing) adj10 (semiconductor or wafer or electronic or substrate or silicon or workpiece)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
7	BRS	L7	210	(carbon adj dioxide or "CO2" or "CO.sub.2") adj (gas or gaseous or vapor) same 16	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB
8	BRS	L8	70604	(dry or drying or dryer or dried) adj10 (semiconductor or wafer or electronic or substrate or silicon or workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB
9	BRS	L9	67	(carbon adj dioxide or "CO2" or "CO.sub.2") adj (gas or gaseous or vapor) same 18	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB

	Type	L #	Hits	Search Text	DBs
10	BRS	L10	17	17 same 19	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
11	BRS	L11	100927	(reduce or reducing or reduce or reduction or inhibit or inhibiting or inhibited or inhibition or lower or lowering or lowered or lowering or minimize or minimizing or minimized or eliminate or eliminating or eliminated or elimination) adj10 (charge or charge adj3 buildup or charge adj3 build-up or electric adj3 (charge or discharge) or electrostatic adj3 (charge or discharge) or "ESD" or electricity or static adj electricity or electrostatic adj3 electricity)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
12	BRS	L12	2001	(carbon adj dioxide or "CO2" or "CO.sub.2") same 16	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
13	BRS	L13	12	l12 same l11	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
14	BRS	L14	6	l12 and l11 and l9	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
15	BRS	L15	126336	(reduce or reducing or reduce or reduction or inhibit or inhibiting or inhibited or inhibition or lower or lowering or lowered or lowering or minimize or minimizing or minimized or eliminate or eliminating or eliminated or elimination or smaller) adj10 (charge or charge adj3 buildup or charge adj3 build-up or charge-up or resistivity or electric adj3 (charge or discharge) or electrostatic adj3 (charge or discharge) or "ESD" or electricity or static adj electricity or electrostatic adj3 electricity)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
16	BRS	L16	769439	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or rinse or rinsed or rinsing or process or processing or processed or strip or stripping or stripped or etch or etching or etched or etchant or wash or washing or washed or dip or dipping or dipped or soak or soaking or soaked or immerse or immersing or immersed or immersion) adj10 (semiconductor or wafer or electronic or substrate or silicon or workpiece)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
17	BRS	L17	5138	(carbon adj dioxide or "CO2" or "CO.sub.2") same 116	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
18	BRS	L18	624	(carbon adj dioxide or "CO2" or "CO.sub.2") same 18	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
19	BRS	L19	70604	(dry or drying or dryer or dried or spin-dry\$3 or spin adj dried or spin adj3 dry\$3 or spin adj3 dried) adj10 (semiconductor or wafer or electronic or substrate or silicon or workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB
20	BRS	L20	624	(carbon adj dioxide or "CO2" or "CO.sub.2") same 119	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB
21	BRS	L21	624	(carbon adj dioxide or "CO2" or "CO.sub.2") same 119	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB

	Type	L #	Hits	Search Text	DBs
22	BRS	L22	26	117 and 115 and 121	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
23	BRS	L23	32270	(nitrogen or "N2" or "N.sub.2") same 116	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
24	BRS	L24	1213	123 and 111	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
25	BRS	L25	89	124 and (isopropyl adj alcohol or isopropanol or "IPA")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
26	BRS	L26	39	117 and 115 and (isopropyl adj alcohol or isopropanol or "IPA")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
27	BRS	L27	1626	119 same (isopropyl adj alcohol or isopropanol or "IPA")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
28	BRS	L28	6	117 and 115 and 127	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
29	BRS	L29	48	117 and 120 and 127	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
30	BRS	L30	11	119 same (isopropyl adj alcohol or isopropanol or "IPA") same (carbon adj dioxide or "CO2" or "CO.sub.2") same (nitrogen or "N2" or "N.sub.2")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
31	BRS	L31	136	119 same (carbon adj dioxide or "CO2" or "CO.sub.2") same (nitrogen or "N2" or "N.sub.2")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
32	BRS	L32	11	131 and 115	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
33	BRS	L34	0	133 and 115	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
34	BRS	L33	28	119 same (isopropyl adj alcohol or isopropanol or "IPA") same (carbon adj dioxide or "CO2" or "CO.sub.2")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
35	BRS	L35	226	116 same (ionized or ionizing or ionization or ionize) adj2 (air or clean adj dry adj air or dry adj air or oxygen or "O2" or "O.sub.2")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
36	BRS	L37	0	135 and 133	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
37	BRS	L36	17	l19 same (ionized or ionizing or ionization or ionize) adj2 (air or clean adj dry adj air or dry adj air or oxygen or "O2" or "O.sub.2")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
38	BRS	L38	34	l19 same (ionized or ionizing or ionization or ionize or ionizable) adj10 (air or clean adj3 dry adj3 air or dry adj3 air or oxygen or "O2" or "O.sub.2" or air3 adj stream)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
39	BRS	L39	5	(carbon adj dioxide or "CO2" or "CO.sub.2") same 135	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
40	BRS	L40	20	(carbon adj dioxide or "CO2" or "CO.sub.2") and 135	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB
41	BRS	L41	99	115 and (carbon adj dioxide or "CO2" or "CO.sub.2") and (ionized or ionizing or ionization or ionize or ionizable) adj10 (air or clean adj3 dry adj3 air or dry adj3 air or oxygen or "O2" or "O.sub.2" or air3 adj stream)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB
42	BRS	L42	335	(carbon adj dioxide or "CO2" or "CO.sub.2") same (ionized or ionizing or ionization or ionize or ionizable) adj10 (air or clean adj3 dry adj3 air or dry adj3 air or oxygen or "O2" or "O.sub.2" or air3 adj stream)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB

	Type	L #	Hits	Search Text	DBs
43	BRS	L43	22	142 and 115	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B